

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of)
Takahashi Migaku) Group:
Serial No.:)
Filed:) Examiner
Title: MAGNETIC THIN FILM AND)
PRODUCTION METHOD THEREFOR)

#2/Pre A
5/99

PRELIMINARY AMENDMENT

Hon. Commissioner of Patents
and Trademarks
Washington, D.C. 20231

Sir:

Please enter the following Amendments to the application prior to
calculating the filing fee.

IN THE CLAIMS

1. A magnetic thin film [, characterized in] comprising:
an iron nitride thin film having a nitrogen martensite α'
phase with α (002) surface formed on a substrate using an opposed-
target DC sputtering method by means of reactive sputtering with N_2
gas;
said α' phase having diffraction rays observed from only
said α (002) surface.
2. A magnetic thin film[, characterized in that] comprising:
iron (α - Fe) thin films and iron nitride thin films [are]
alternately deposited on a substrate by means of an opposed-target
DC sputtering method, said iron nitride thin films having a nitrogen
martensite α' phase with α (002) surface, said α' phase having
diffraction rays observed only from said α (002) surface.

Please delete Claims 3-9.

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